

SOEI/0057 UNASSIGNED

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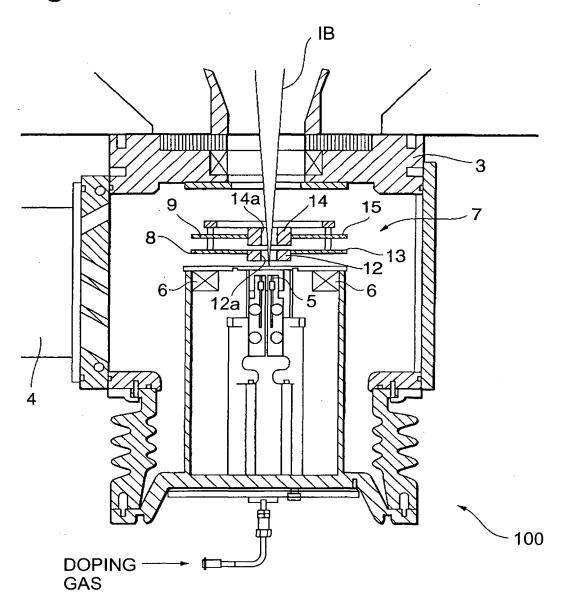
ATTY DKT. NO.: U.S. SERIAL NO.: FILED: APPLICANT: TITLE:

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HEREWITH
APPLIED MATERIALS, INC.
ION IMPLANTATION METHOD, SOI WAFER MANUFACTURING METHOD
AND ION IMPLANTATION SYSTEM

INVENTOR:

ITO, ET AL.

Fig.2



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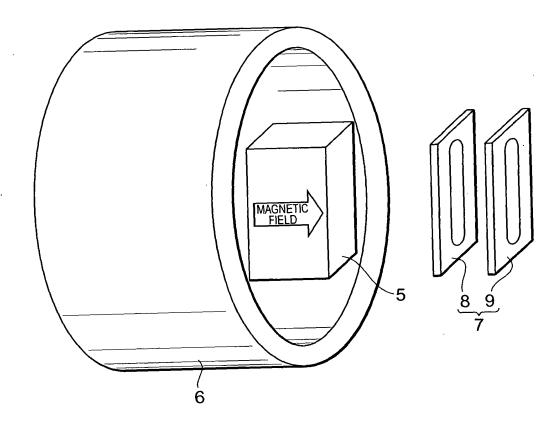
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Fig.3



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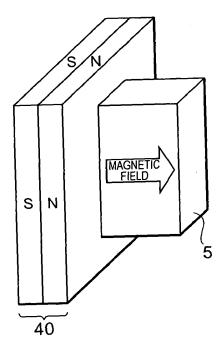
ITO, ET AL.

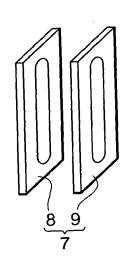
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Fig.4





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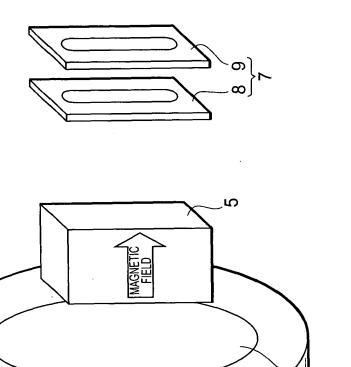


Fig.5

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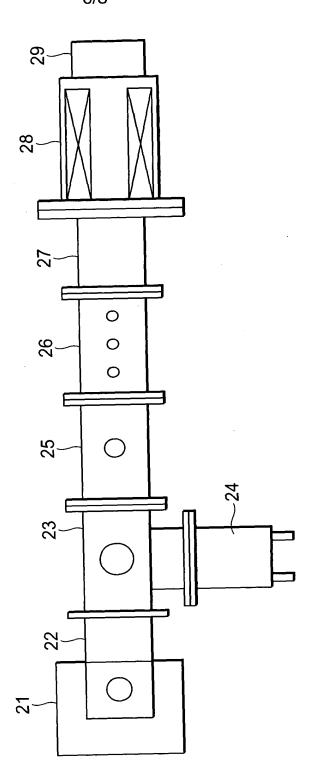
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INVENTOR: ITO, ET AL.

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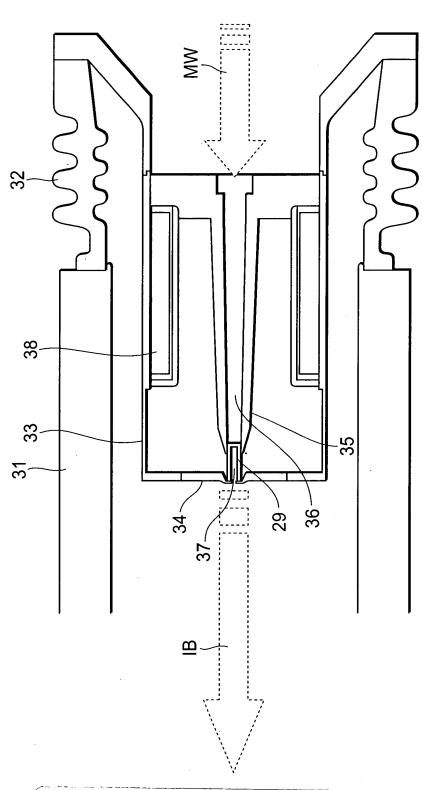
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